Page 1 FORM PTO (449 (Modified) ATTY. DOCKET NO. SERIAL NO. FIS9-2003-0235US1 10/707,841 LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT: APPLICANT'S INFORMATION DISCLOSURE Haining S. Yang, et al. **STATEMENT** (Use several sheets if necessary) FILING DATE: GROUP: Unassigned 3/) 01/16/2004 REFERENCE DESIGNATION U.S. PATENT DOCUMENTS **EXAMINER DOCUMENT** FILING DATE INITIALS NUMBER. DATE NAME **CLASS SUBCLASS** (IF APPRO.) /JC/ 6,228,694 B1 5/8/2001 Doyle et al. 6,406,973 B1 6/18/2002 Lee 6,281,532 B1 8/28/2001 Doyle et al. 5,683,934 11/4/97 Candelaria 6,368,931 B1 4/9/2002 Kuhn, et al. 5,310,446 5/10/94 Konishi et al. 4,853,076 8/1/89 Tsaur et al. US 2002/0090791 A1 7/11/2002 Doyle et al. US 2002/0074598 A1 6/20/2002 Doyle et al. 6,509,618 B2 of:/21/2003 Jan et al. 6,476,462 B2 11/5/2002 Shimizu et al. /JC/ 6,362,082 B1 3/26/2002 Doyle et al. /JC/ 5,565,697 10/15/96 Asakawa et al. US 2003/0040158 A1 2/27/2003 Saitoh US 2002/0086472 A1 7/4/2002 Roberds et al. 6,521,964 B1 2/18/2003 Jan et al. /JC/ 6,506,652 01/14/03 Jan, et al. FOREIGN PATENT DOCUMENTS **DOCUMENT TRANSLATION** NUMBER DATE **COUNTRY CLASS** SUBCLASS YES NO

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